

IN THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) A manufacturing method of a display device in a plasma treatment chamber comprising the step of:

partially forming a conductor film over a substrate;
forming a resist mask by use of liquid droplet jetting means, over the conductor film;
forming a wiring by partially etching the conductor film over the substrate by discharging a plasma to the plasma treatment chamber from a plasma treatment means having one set of electrodes contained therein for generating the plasma at a pressure of 5 to 800 Torr from a first reactive gas introduced to the plasma treatment means;

after switching the first reactive gas to a second reactive gas, partially ashing the resist mask by discharging a plasma to the plasma treatment chamber from the plasma treatment means ~~partially blowing the second reactive gas~~ in the plasma treatment chamber at the pressure of 5 to 800 Torr from the second reactive gas introduced to the plasma treatment means;

providing the plasma treatment means in the plasma treatment chamber;
providing one electrode of the set of electrodes which surrounds an other electrode of the set of electrodes; and
providing a distal portion of the one electrode of the set of electrodes being pointed toward the other electrode of the set of electrodes ,
wherein the distal portion of the one electrode of the set of electrodes has a sharp angle shape.

2. (Currently Amended) A manufacturing method of a display device in a plasma treatment chamber comprising the step of:

partially forming a conductor film over a substrate;
forming a resist mask by use of liquid droplet jetting means, over the conductor film;
forming a wiring by partially etching the conductor film over the substrate by discharging a plasma to the plasma treatment chamber from a plasma treatment means having a plurality of sets of electrodes contained therein for generating the plasma at a pressure of 5 to 800 Torr from a first reactive gas introduced to the plasma treatment means;

after switching the first reactive gas to a second reactive gas, partially ashing the resist

mask by discharging a plasma to the plasma treatment chamber from the plasma treatment means ~~partially blowing the second reactive gas~~ in the plasma treatment chamber at the pressure of 5 to 800 Torr from the second reactive gas introduced to the plasma treatment means;

providing the plasma treatment means in the plasma treatment chamber;

providing one electrode of the plurality of sets of electrodes which surrounds an other electrode of the plurality of sets of electrodes, respectively; and

providing a distal portion of the one electrode of the plurality of sets of electrodes being pointed toward the other electrode of the plurality of sets of electrodes , respectively,

wherein the distal portion of the one electrode of the plurality of sets of electrodes has a sharp angle shape.

3. (Canceled)

4. (Currently Amended) A manufacturing method of a display device comprising the steps of:

forming a conductor film over a substrate;

forming a resist mask over the conductor film;

partially etching the conductor film at a pressure of 5 to 800 Torr by discharging a plasma to a plasma treatment chamber from a plasma treatment means having one set of electrodes contained therein for generating the plasma from a first reactive gas introduced to the plasma treatment means, over the resist mask thereby forming a wiring;

after switching the first reactive gas to a second reactive gas, partially ashing the resist mask by discharging a plasma to the plasma treatment chamber from the plasma treatment means ~~partially blowing the second reactive gas~~ in the plasma treatment chamber at the pressure of 5 to 800 Torr from the second reactive gas introduced to the plasma treatment means;

providing the plasma treatment means in the plasma treatment chamber;

providing one electrode of the set of electrodes which surrounds an other electrode of the set of electrodes; and

providing a distal portion of the one electrode of the set of electrodes being pointed toward the other electrode of the set of electrodes ,

wherein the distal portion of the one electrode of the set of electrodes has a sharp angle shape.

5. (Currently Amended) A manufacturing method of a display device comprising the steps of:
- forming a conductor film over a substrate;
 - forming a resist mask over the conductor film;
 - partially etching the conductor film at a pressure of 5 to 800 Torr by discharging a plasma to a plasma treatment chamber from a plasma treatment means having a plurality of sets of electrodes contained therein for generating the plasma from a first reactive gas introduced to the plasma treatment means, over the resist mask thereby forming a wiring;
 - after switching the first reactive gas to a second reactive gas, partially ashing the resist mask by discharging a plasma to the plasma treatment chamber from the plasma treatment means ~~partially blowing the second reactive gas~~ in the plasma treatment chamber at the pressure of 5 to 800 Torr from the second reactive gas introduced to the plasma treatment means;
 - providing the plasma treatment means in the plasma treatment chamber;
 - providing one electrode of the plurality of sets of electrodes which surrounds an other electrode of the plurality of sets of electrodes, respectively; and
 - providing a distal portion of the one electrode of the plurality of sets of electrodes being pointed toward the other electrode of the plurality of sets of electrodes , respectively,
 - wherein the distal portion of the one electrode of the plurality of sets of electrodes has a sharp angle shape.
6. (Previously Presented) The manufacturing method of the display device according to any of claims 1, 2, 4 and 5, wherein the substrate has a size of 1,000 x 1,200 mm² or more.
7. (Previously Presented) The manufacturing method of the display device according to any of claims 1, 2, 4 and 5, wherein the plasma treatment means scans the substrate in one direction.
8. (Previously Presented) The manufacturing method of the display device according to any of claims 1, 2, 4 and 5, wherein the plasma treatment means alternately scans the substrate in a row direction and in a column direction.
9. (Previously Presented) The manufacturing method of the display device according to any of claims 4 and 5, wherein the resist mask is formed by use of liquid droplet jetting means.

10-11. (Canceled)

12. (Previously Presented) The manufacturing method of the display device according to any of claims 1, 2, 4 and 5, further comprising:
moving the plasma treatment means along a rail.